

FORM PTO-1449 (REV. 7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. 10/620,782	APPLICATION NO. 501085.02
INFORMATION DISCLOSURE STATEMENT <i>(Use several sheets if necessary)</i>		APPLICANT(S) Dirk J. Sundt et al.	
		FILING DATE July 15, 2003	GROUP ART UNIT Not Yet Assigned

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
SM	AA	6,177,331 B1	01/23/01	Koga	438	424	
SM	AB	6,548,371 B2	04/15/03	Fujimaki	438	424	
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AK							
	AL							
	AM							
	AN							
	AO							

OTHER PRIOR ART *(Including Author, Title, Date, Pertinent Pages, Etc.)*

SM	AP	Cheung, N., Lecture notes (handout) EE 143, Lecture 15, University of California Berkely, 2000.
SM	AQ	Clark, S., "Chemical Etching of Silicon Nitride (Si ₃ N ₄) with Hot Phosphoric Acid (H ₃ PO ₄)", Bold Technologies Technical Paper, 2000, pp. 1-6.
	AR	

EXAMINER

Shuman Magee

DATE CONSIDERED

09/09/04

* EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).